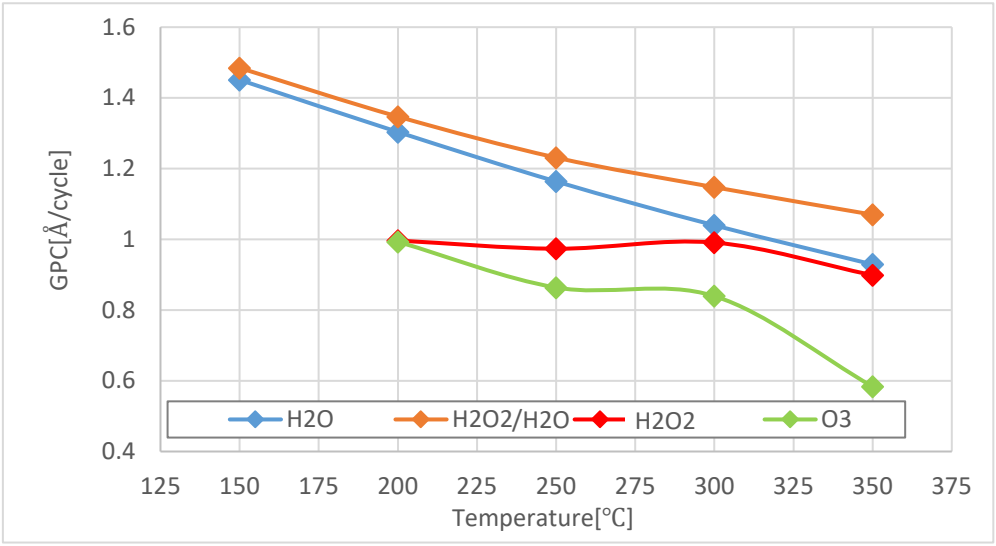

Figure 1. ALD Growth rates for Al_2O_3: H_2O_2/H_2O >H_2O>H_2O_2>O_3.

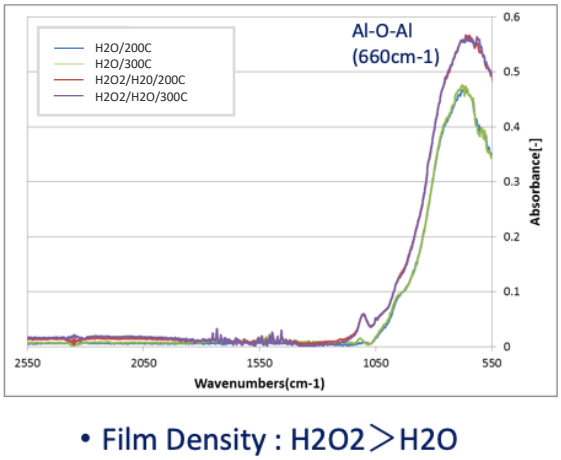

Figure 2. FT-IR of Al_2O_3 films grown with H_2O_2/H_2O vs H_2O, strong signal for hydrogen peroxide films implies higher density. Spectra are normalized with film thickness.

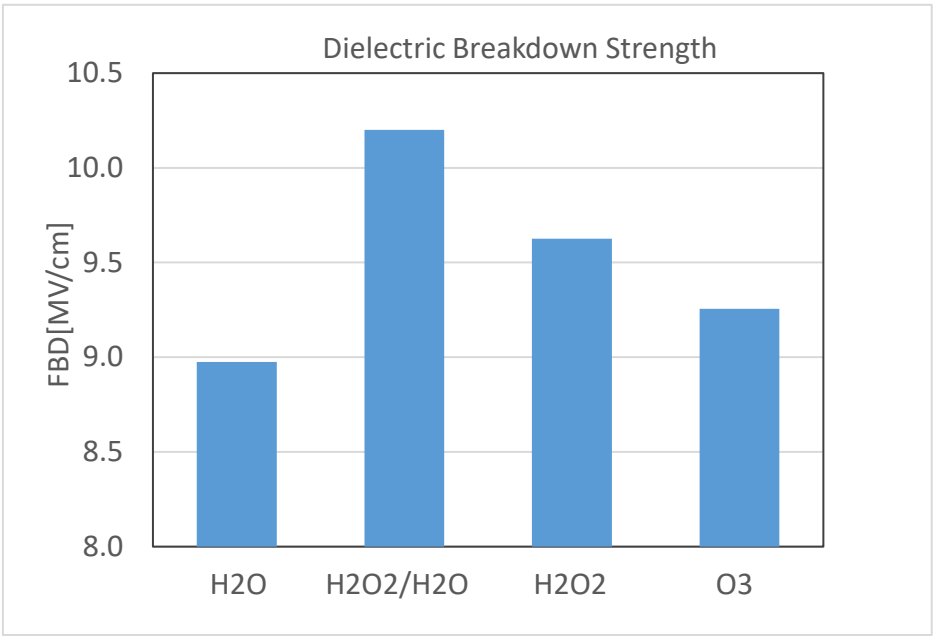

Figure 3. Dielectric Breakdown Strength measurement comparing films grown by all three oxidants. Hydrogen peroxide based film shows a significant increase in this electrical property where H_2O_2/H_2O > H_2O_2 > O_3 > H_2O.